

IN THE CLAIMS:

Please substitute the following amended claims for the corresponding original claims. A marked copy of the claim amendments is attached hereto.

1. (amended five times) A process chamber for processing a substrate in a process gas and reducing emissions of hazardous gas to the environment, the process chamber comprising:

- (a) a support capable of supporting the substrate;
- (b) a gas distributor capable of introducing process gas into the process chamber;
- (c) a gas activator capable of activating the process gas to perform a process in the process chamber thereby forming effluent containing hazardous gas;
- (d) an exhaust tube through which the effluent may be flowed, the exhaust tube being substantially absent projections or recesses that alter the flow direction of a majority of effluent flowing past the projections or recesses away from a general flow direction of the effluent through the exhaust tube; and
- (e) a microwave energy applicator to couple microwaves to the effluent flowing through the exhaust tube to reduce the hazardous gas content of the effluent.

40. (once amended) The apparatus of claim 10 wherein the exhaust tube is substantially absent projections or recesses that alter the flow direction of a majority of effluent flowing past the projections or recesses away from a general flow direction of the effluent through the exhaust tube.

47. (once amended) The apparatus of claim 46 wherein the sapphire comprises monocrystalline sapphire.

50. (once amended) The process chamber of claim 11 wherein the exhaust tube is substantially absent projections or recesses that alter the flow direction of a majority of effluent flowing past the projections or recesses away from a general flow direction of the effluent through the exhaust tube.

56. (once amended) The process chamber of claim 24 wherein the exhaust tube is substantially absent projections or recesses that alter the flow direction of a majority of effluent flowing past the projections or recesses away from a general flow direction of the effluent through the exhaust tube.

66. (once amended) The process chamber of claim 26 wherein the exhaust tube is substantially absent projections or recesses that alter the flow direction of a majority of effluent flowing past the projections or recesses away from a general flow direction of the effluent through the exhaust tube.

Please add the following new claims:

79. (new) A process chamber for processing a substrate in a process gas and reducing emissions of hazardous gas to the environment, the process chamber comprising:

- (a) a support capable of supporting the substrate;
- (b) a gas distributor capable of introducing process gas into the process chamber;
- (c) a gas activator capable of activating the process gas to perform a process in the process chamber thereby forming effluent containing hazardous gas;
- (d) an exhaust tube through which the effluent may be flowed, the exhaust tube being adapted to provide a non-circuitous flow of effluent therethrough; and
- (e) a microwave energy applicator to couple microwaves to the effluent flowing through the exhaust tube to reduce the hazardous gas content of the effluent.

80. (new) The process chamber of claim 79 wherein the exhaust tube is substantially absent projections or recesses that alter the flow direction of a majority of effluent flowing past the projections or recesses away from a general flow direction of the effluent through the exhaust tube.

81. (new) The process chamber of claim 79 wherein the exhaust tube comprises sapphire.

82. (new) The process chamber of claim 79 wherein the exhaust tube is adapted to provide a laminar flow of effluent therethrough.

83. (new) The process chamber of claim 82 wherein the exhaust tube comprises a cylinder having an axis parallel to the direction of flow of the effluent through the tube.